

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

KOBAYASHI, S.

Atty. Ref.: 900-471

Appl. No. To be assigned

Group:

Filed: August 4, 2003

Examiner:

For: MASK PATTERN AND METHOD FOR FORMING RESIST PATTERN USING
MASK PATTERN THEREOF

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August 4, 2003

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

PRELIMINARY AMENDMENT

In order to place the above-identified application in better condition for
examination, please amend the application as follows: